
Symposium (Oral) | Symposium | Toward future applications of oxides electronics; past, present and future

[13p-A22-1~5]Toward future applications of oxides electronics; past, present and future

Hiroyuki Akinaga(AIST), Toshiyuki Kawaharamura(Kochi Univ. of Tech.)

Tue. Sep 13, 2016 1:15 PM - 6:15 PM A22 (Main Hall B)

△ : Presentation by Applicant for JSAP Young Scientists Presentation Award

▲ : English Presentation

▼ : Both of Above

No Mark : None of Above

2:15 PM - 3:15 PM

[13p-A22-2]*How we learned to stop worrying and love the High-k.*

○Noburu Fukushima¹ (1.Toshiba RDC)

Keywords:semiconductors, high-k dielectrics, oxide electronics

Introduction of high-k dielectrics to memory capacitors and advanced gate insulators had been intensively studied to pursuit the ultimate scaling. We will discuss how we had learned to solve the problems such as compatibility with the current process, the difficulty in the interface control. Such research and development and their results would be most important to implement the oxide electronics to the future devices. In addition, they will bring more insights regarding what the oxide electronics should promote for further functionality or novel values beyond the scaling.